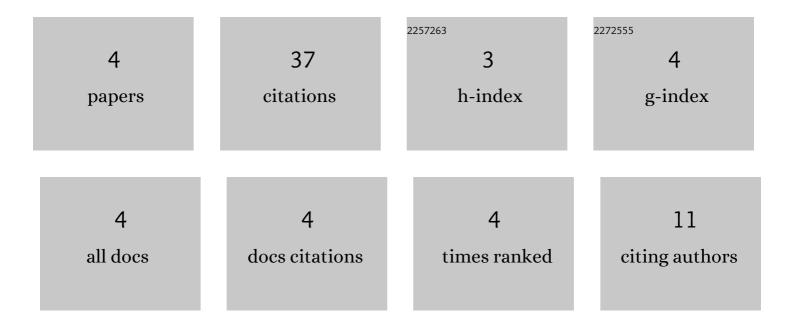
Kazuki Azumagawa

List of Publications by Year in descending order

Source: https://exaly.com/author-pdf/3302024/publications.pdf

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#	Article	IF	Citations
1	Application of machine learning to stochastic effect analysis of chemically amplified resists used for extreme ultraviolet lithography. Japanese Journal of Applied Physics, 2021, 60, SCCC02.	0.8	16
2	Analysis of dissolution kinetics of narrow polydispersity poly(4-hydroxystyrene) in alkaline aqueous solution using machine learning. Japanese Journal of Applied Physics, 2021, 60, 066503.	0.8	9
3	Analysis of trade-off relationships between resolution, line edge roughness, and sensitivity in extreme ultraviolet lithography using lasso regression. Japanese Journal of Applied Physics, 2020, 59, 076501.	0.8	7
4	Regression analysis of photodecomposable quencher concentration effects on chemical gradient in chemically amplified extreme ultraviolet resist processes. Japanese Journal of Applied Physics, 2020, 59, 116505.	0.8	5